ESc201: Introduction to Electronics

Metal Oxide Semiconductor Field-Effect Transistors (MOSFETs)

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Introduction

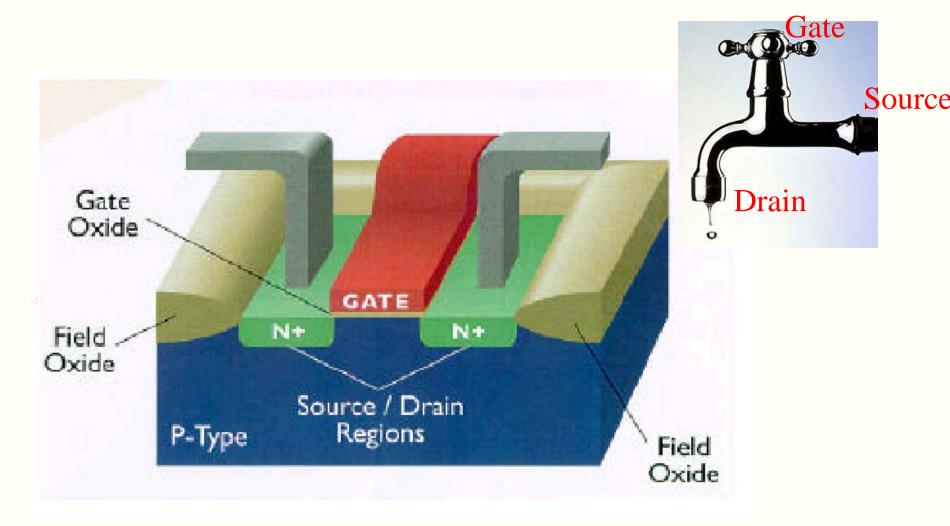
Classification of MOSFET

P channel
 ✓ Enhancement type
 ✓ Depletion type
 N channel
 ✓ Enhancement type
 ✓ Depletion type

Widely used in IC circuits

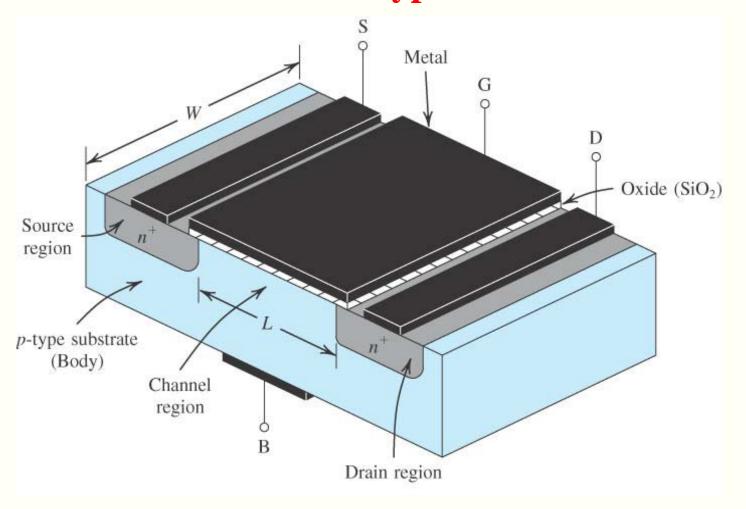
MOSFET

Metal Oxide Semiconductor Field Effect Transistor



An NMOSFET

Device Structure of Enhancement-Type NMOS

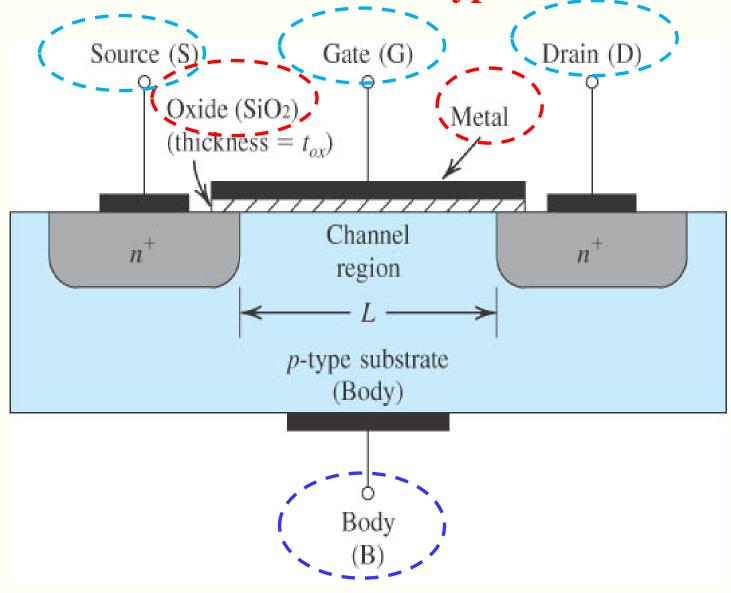


L: 1 to 10 µm

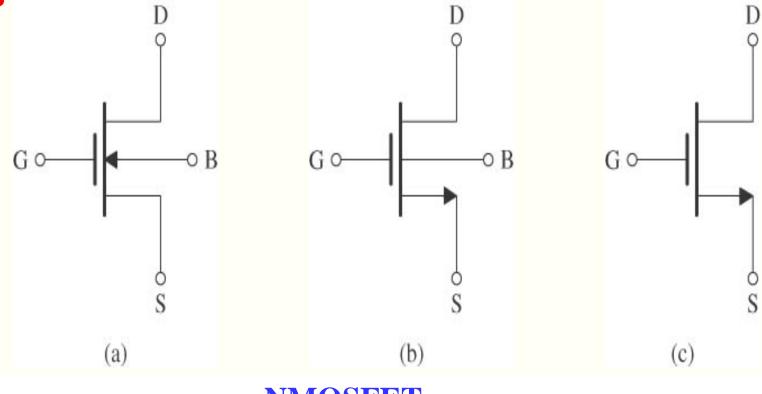
W: 2 to 500 µm

Thickness of oxide layer: 0.02 to 0.1 µm

Device Structure of Enhancement-Type NMOS



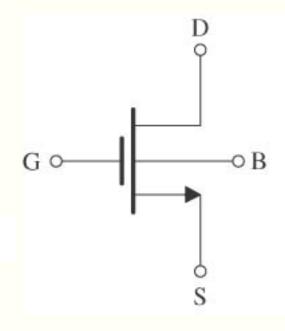
Symbols

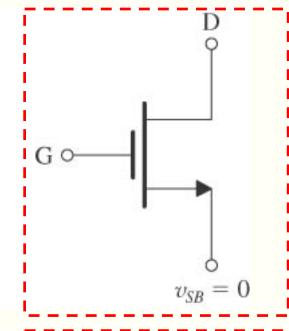


NMOSFET

- (a) Circuit symbol for the *n*-channel enhancement-type MOSFET.
- (b) Modified circuit symbol with an arrowhead on the source terminal to distinguish it from the drain and to indicate device polarity (i.e., *n* channel).
- (c) Simplified circuit symbol to be used when the source is connected to the body or when the effect of the body on device operation is unimportant.

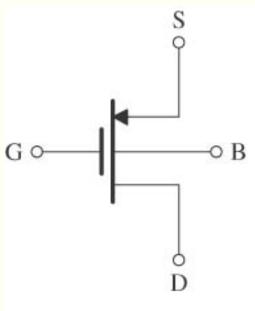
Symbols

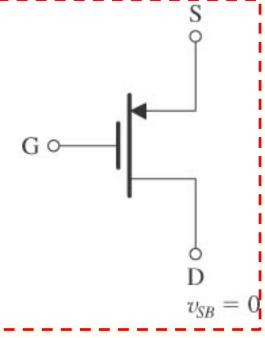




Mostly Used

NMOSFET



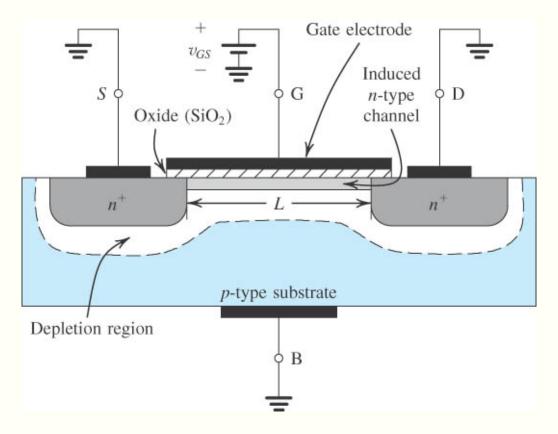


PMOSFET

Physical Operation

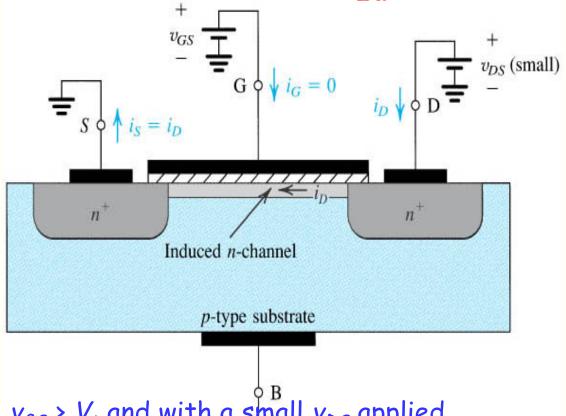
- Creating an *n* channel
- Drain current controlled by v_{DS}
- Drain current controlled by v_{GS}

Creating a Channel for Current Flow



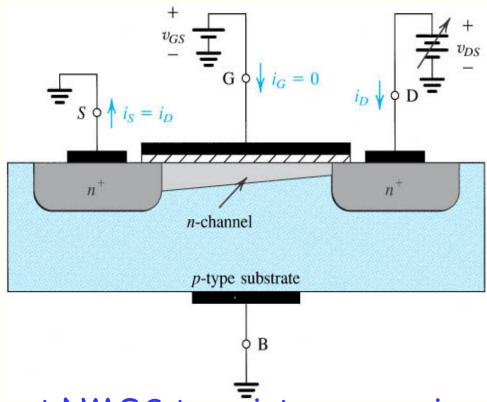
- The enhancement-type NMOS transistor with a positive voltage applied to the gate.
- \succ An *n* channel is induced at the top of the substrate beneath the gate.

Drain Current Controlled by Small Voltage v_{DS}



- > An NMOS transistor with $v_{GS} > V_t$ and with a small v_{DS} applied.
- > The channel depth is uniform.
- > The device acts as a resistance.
- > The channel conductance is proportional to effective voltage.
- \succ Drain current is proportional to $(v_{GS} V_t) v_{DS}$.

v_{DS} is increased



- \triangleright Operation of the enhancement NMOS transistor as v_{DS} is increased.
- > The induced channel acquires a tapered shape.
- \succ Channel resistance increases as v_{DS} is increased.
- >Drain current is controlled by both of the two voltages.

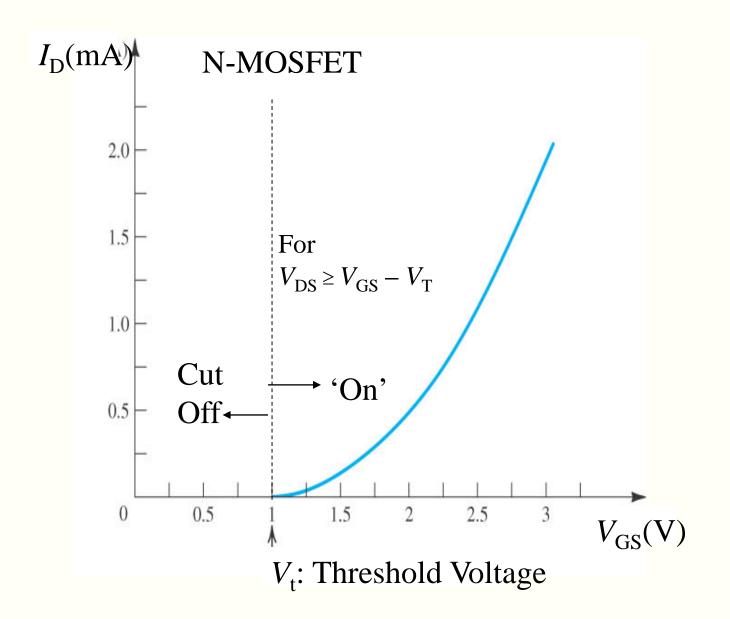
Channel Pinch- Off

- · Channel is pinched off
 - > Inversion layer disappeared at the drain point
 - > Drain current is n't disappeared
- Drain current is saturated and only controlled by the v_{GS}
- Triode region and saturation region

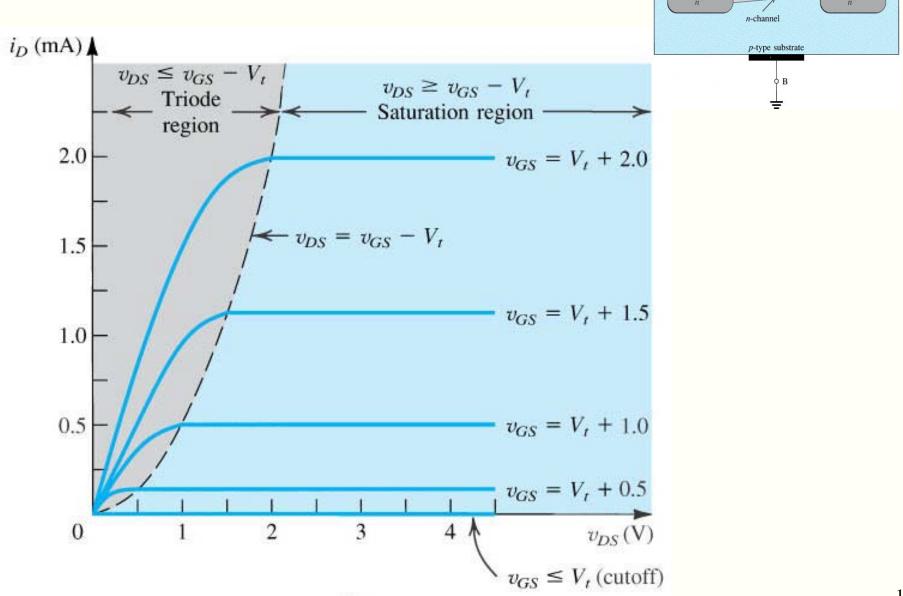
Drain Current Controlled by v_{GS}

- v_{GS} creates the channel.
- Increasing v_{GS} will increase the conductance of the channel.
- At saturation region only the v_{GS} controls the drain current.
- At subthreshold region, drain current has the exponential relationship with $v_{\mathcal{GS}}$

Transfer Characteristics



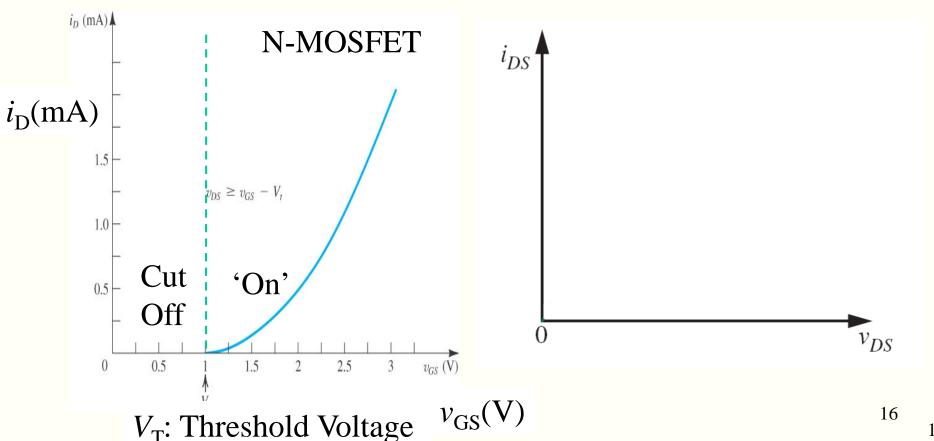
I-V Characteristics



 $\begin{array}{c}
+ \\
v_{GS} \\
- \\
\hline
G \\
\downarrow v_{G} = 0
\end{array}$

Regions of Transistor 'Operation'

- Cut off region $(v_{GS} < V_t)$
 - Input voltage less than threshold voltage



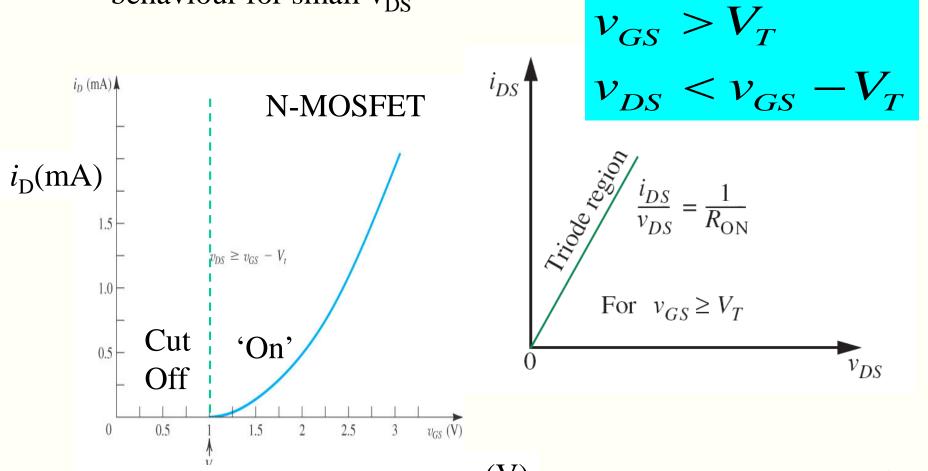
Regions of Transistor 'Operation'

• Triode region ($v_{GS} > V_{T}$ and $v_{DS} < v_{GS} - V_{T}$)

- Linear relationship between i_{DS} and v_{DS} reflects resistive

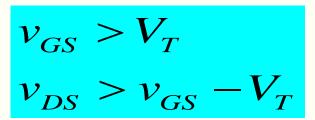
behaviour for small v_{DS}

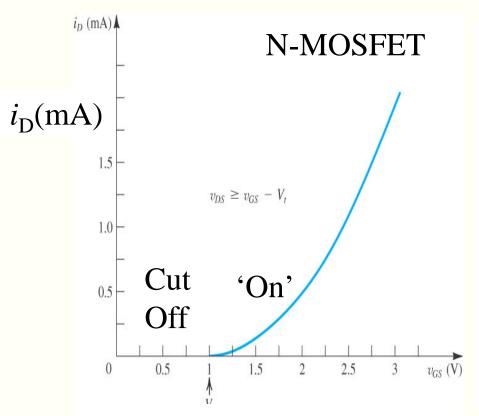
 $V_{\rm T}$: Threshold Voltage

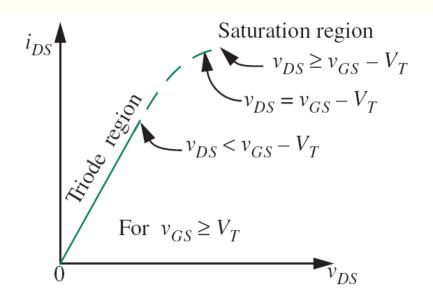


Regions of Transistor 'Operation'

- Saturation region $(v_{GS} > V_T \text{ and } v_{DS} \ge v_{GS} V_T)$
 - Transistor is 'on'
 - Drain bias is above saturation voltage
 - Amplifier should operate in this region



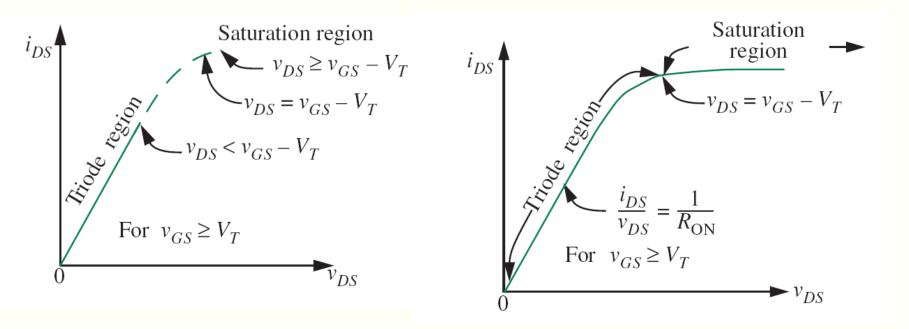




The current i_{DS} begins to saturate as v_{DS} approaches the value of $v_{GS} - V_T$.

 $V_{\rm T}$: Threshold Voltage

Saturation region ($v_{GS} > V_{T}$ and $v_{DS} > v_{GS} - V_{T}$)



The current i_{DS} begins to saturate as v_{DS} approaches the value of $(v_{GS} - V_T)$.

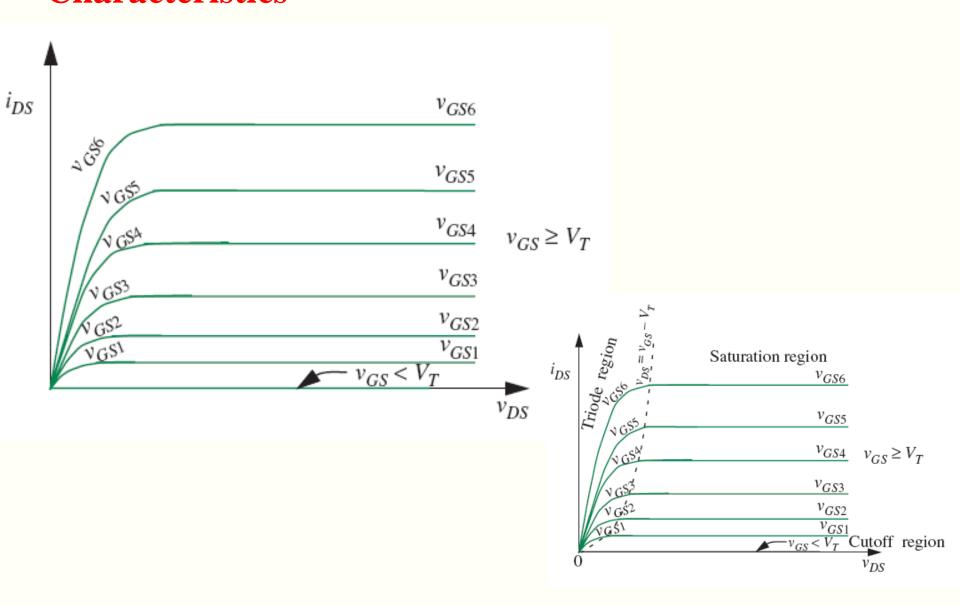
The saturation region of MOSFET Operation

MOSFET operates in saturation region when following

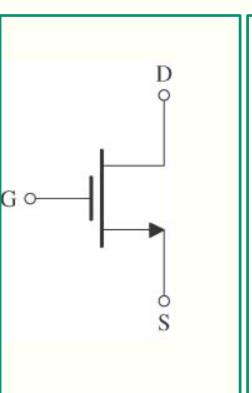
two conditions are met:

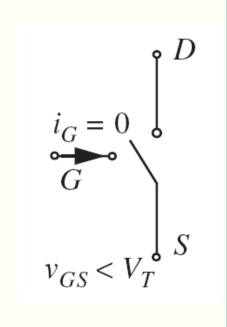
$$v_{GS} > V_T$$
 $v_{DS} > v_{GS} - V_T$

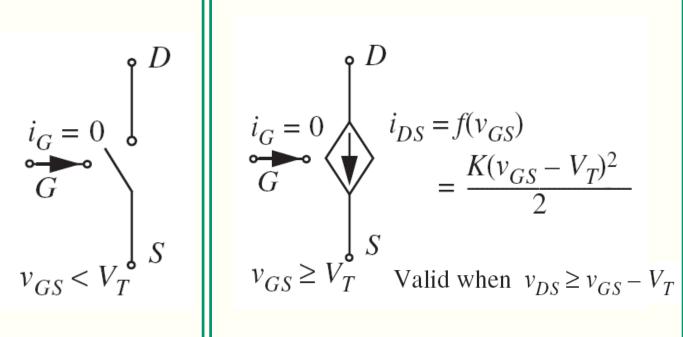
Different values of $v_{\rm GS}$ (> $V_{\rm t}$) provides different $i_{\rm DS}$ and $v_{\rm DS}$ Characteristics



The Switch Current Source MOSFET Model





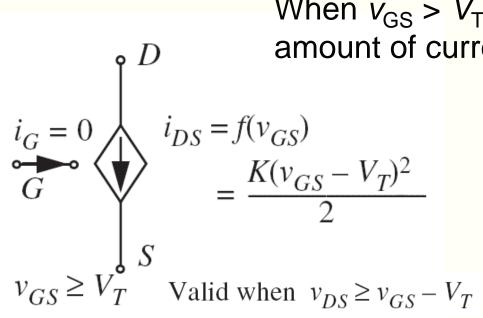


MOS Device

Open State

Closed State

The Switch Current Source MOSFET Model



When
$$v_{GS} > V_{T}$$
 and $v_{DS} > v_{GS} - V_{T}$ the amount of current provided by the source is

$$i_D = \frac{K}{2} \left(v_{GS} - V_T \right)^2$$

Unit of K: A/V²

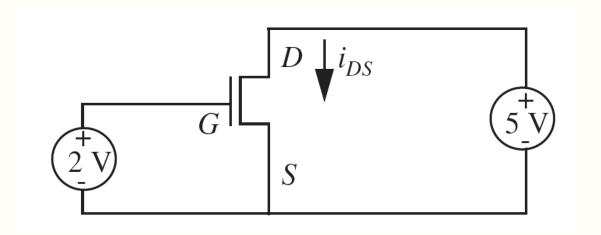
where
$$K = k_n' \frac{W}{L} = \mu_n C_{ox}$$
 W: gate width; L: gate Length

k'_n: Constant related to MOSFET properties (A/V²)

µ_n: Electron mobility in channel

Cox: Capacitance per unit area of parallel plate capacitor by gate electrode and channels

Example-1: Determine the current i_{DS} for the circuit shown below. Assume: $K = 1 \text{mA/V}^2$ and $V_T = 1 \text{V}$

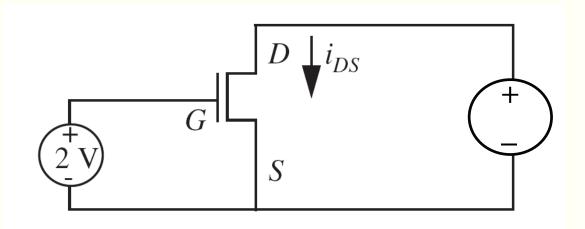


$$i_D = \frac{K}{2} \left(v_{GS} - V_T \right)^2$$

$$i_D = \frac{1}{2} (2 - 1)^2$$

$$i_D = 0.5$$
 mA

Example-2: Assume: $K = 1 \text{mA/V}^2$ and $V_T = 1 \text{V}$



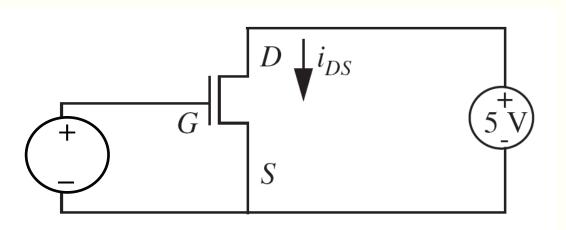
What should be the minimum value of the drain to source v_{DS} for which MOSFET will operate in saturation region. (Assume V_{GS} is 2V)

For the MOSFET to operate in saturation:

$$egin{aligned}
u_{GS} > V_T \
u_{DS} >
u_{GS} - V_T \end{aligned}$$

$$v_{DS} > 1$$
 V

Example-3: Assume: $K = 1 \text{mA/V}^2$ and $V_T = 1 \text{V}$



What is maximum value of v_{GS} for which MOSFET will operate in saturation region

For the MOSFET to operate in saturation:

$$\begin{aligned} v_{GS} > V_T \\ v_{DS} > v_{GS} - V_T \end{aligned} \qquad 5$$

$$5 > v_{GS} - 1$$

$$v_{GS} < 6 \quad V$$

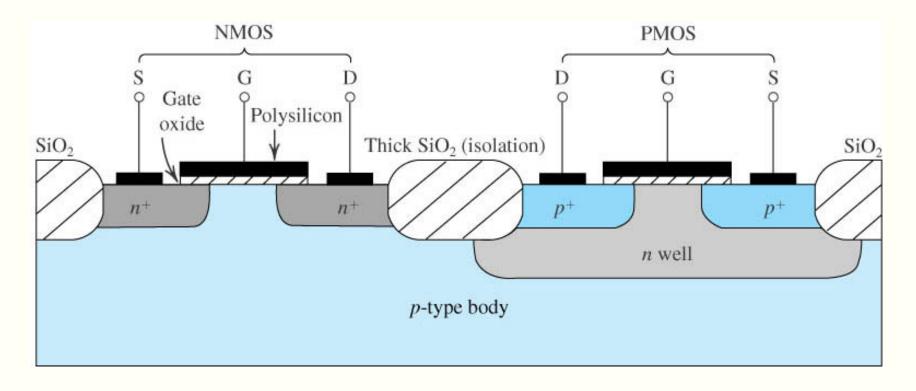
$$v_{GS} > 1$$
 V

$$1 V < v_{GS} < 6 V$$

p Channel Device

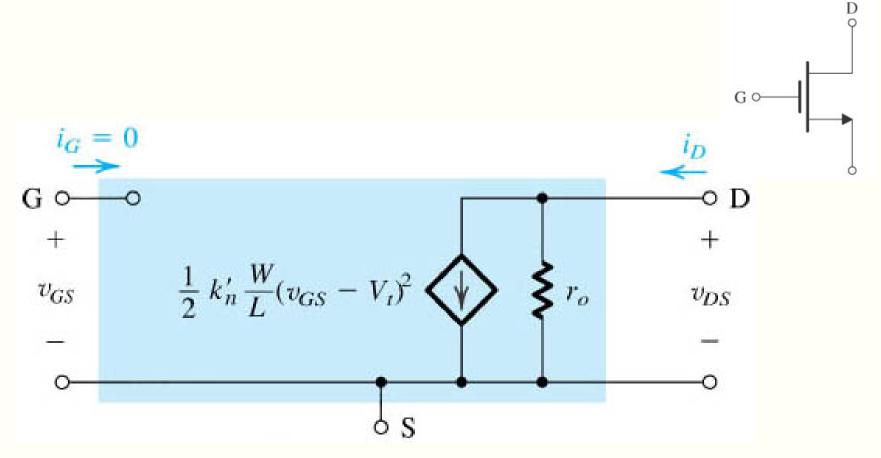
- Structure of p channel device
 - The substrate is *n* type and the inversion layer is *p* type.
 - > Carrier is hole.
 - > Threshold voltage is negative.
 - \triangleright All the voltages and currents are opposite to the ones of n channel device.
 - Physical operation is similar to that of n channel device.

Complementary MOS or CMOS



- \triangleright The PMOS transistor is formed in n well.
- Another arrangement is also possible in which an n-type body is used and the n device is formed in a p well.
- >CMOS is the most widely used of all the analog and digital IC circuits.

Large Signal Equivalent Circuit Model for NMOS



Large Signal Equivalent circuit model of the *n*-channel MOSFET in saturation, incorporating the output resistance r_o . The output resistance models the linear dependence of i_D on v_{DS}

MOSFET Circuit: DC Analysis

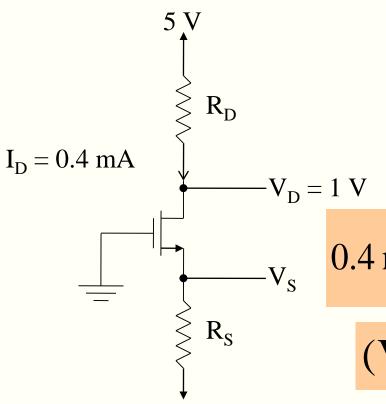
- a. Assuming device operates in saturation thus i_D satisfies with $i_D \sim v_{GS}$ equation.
- b. According to biasing method, write voltage loop equation.
- c. Combining above two equations and solve these equations.
- d. Usually we can get two value of v_{GS} , only the one of two has physical meaning.
- e. Checking the value of v_{DS}
 - i. if $v_{DS} \ge v_{GS} V_t$, assumption is correct.
 - ii. if $v_{DS} \le v_{GS} V_t$, assumption is not correct.

Example 4 (DC Analysis of MOSFET Circuits)

Design the circuit shown in figure so that the MOSFET operates in saturation region with $I_D = 0.4$ mA and $V_D = 1$ V. The MOSFET has

$$V_t = 2$$
 V, $\mu_n C_{0x} = 20~\mu\text{A/V}^2$, $L = 10~\mu\text{m}$ and $W = 400~\mu\text{m}$.

$$r_0 \rightarrow \infty$$



$$R_{\rm D} = \frac{5-1}{0.4 \, \text{mA}} = 10 \, \text{K}\Omega$$

$$I_{D} = \frac{1}{2} \mu_{0} C_{0x} \frac{W}{L} (V_{GS} - V_{t})^{2}$$

$$0.4 \text{ mA} = \frac{1}{2} 20 \times 10^{-6} \frac{A}{V^2} \cdot \frac{400}{10} (V_{GS} - 2)^2$$

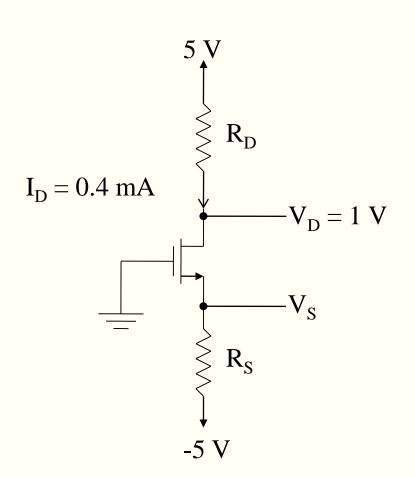
$$(V_{GS} - 2)^2 = 1 \implies V_{GS} - 2 = \pm 1$$

or
$$V_{GS} = +1 \text{ V or } +3 \text{ V}$$

$$V_{GS} = +1 \text{ V or } +3 \text{ V}$$



•The first solution is not consistent with our initial assumption of operation in the saturation mode V_t (=2 V) Therefore



$$V_{GS} = 3 V$$

$$V_{GS} = 3 V$$

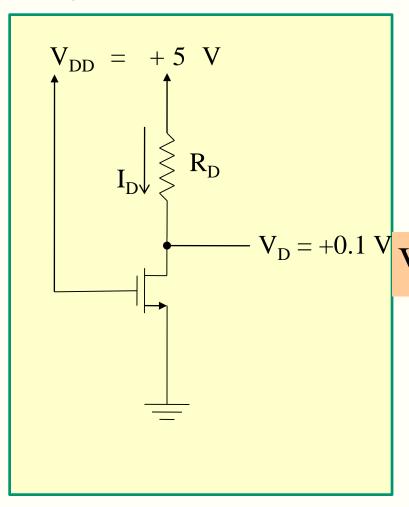
$$\Rightarrow V_{S} = -3 V$$

$$R_{S} = \frac{V_{S} - (-5)}{I_{S}} = \frac{V_{S} + 5}{I_{D}}$$

$$=\frac{-3+5}{0.4\,\mathrm{mA}}=5\,\mathrm{K}\Omega$$

Example 5 (DC Analysis of MOSFET Circuits)

Design the circuit shown in figure for MOSFET to operate in saturation with drain voltage of 0.1 V. Determine R_D . The MOSFET has $V_t = 1 \text{ V}$ and kn $W/L = 1 \text{ mA/V}^2$. Neglect r_0 .



$$egin{aligned}
u_{GS} > V_T \
u_{DS} >
u_{GS} - V_T \
V_T >
u_{GD} \end{aligned}$$

$$V_D = +0.1 \text{ V}$$
 $V_{GS} = 5 \text{ V} \text{ (>V}_T \text{)}$ MOSFET is ON

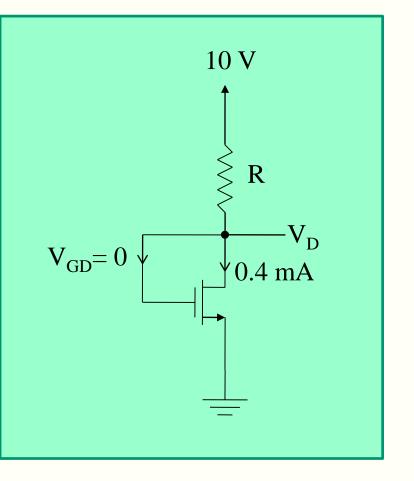
$$V_{GD} = 5 - 0.1 = 4.9 \text{ V}$$

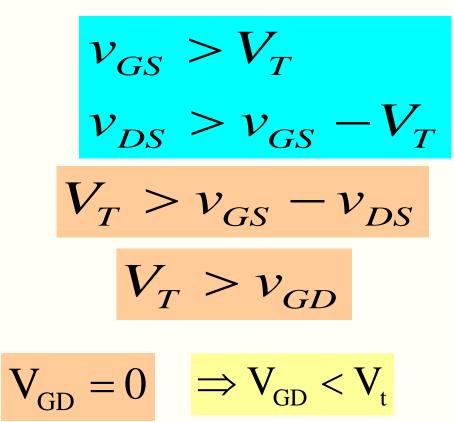
$$V_T < v_{GD}$$

MOSFET is not in saturation

Example 6 (DC Analysis of MOSFET Circuits)

Design the circuit as shown in figure so that the MOSFET operates in saturation region with $I_D=0.4$ mA. The MOSFET has $V_t=2$ V, $\mu_n C_{0x}=20~\mu\text{A/V}^2~$, $L=10~\mu\text{m}$ and $~W=100~\mu\text{m}$. Neglect r_0 .





$$I_D = 0.4 \text{ mA}, V_t = 2 \text{ V}, \mu_n C_{0x} = 20 \mu \text{A/V}^2$$
 $L = 10 \mu \text{m} \text{ and } W = 100 \mu \text{m}.$

$$I_{D} = \frac{1}{2} \mu_{0} C_{0x} \frac{W}{L} (V_{GS} - V_{t})^{2}$$

$$I_{D} = \frac{1}{2} \mu_{0} C_{0x} \frac{W}{L} (V_{GS} - V_{t})^{2} \quad 0.4 \text{ mA} = \frac{1}{2} 20 \times 10^{-6} \cdot \frac{100}{10} (V_{GS} - 2)^{2}$$

$$(V_{GS} - 2)^2 = 4 \quad \Rightarrow \quad V_{GS} - 2 = \pm 2$$

$$V_{GS} = 0$$
 or 4 V

$$\Rightarrow V_{GD} < V_{t}$$



MOSFET is in saturation

$$V_{GS} = 4 V$$

$$\Rightarrow$$
 $V_D = 4 V$

$$R = \frac{10 - V_D}{0.4 \text{ mA}}$$

$$R = \frac{10 - V_D}{0.4 \text{ mA}} = \frac{10 - 4}{0.4 \text{ mA}} = 15 \text{ K}\Omega$$

